JSAP-KPS Joint Symposium - Wide Bandgap Semiconductor Devices -

bandgap semiconductor devices have been studied Wide energetically, and the importance to solve the environmental and energy problems on the earth is increasing. To solve the global problems, cooperation among countries is crucial. symposium, active researchers in the field of wide bandgap semiconductor devices are invited from Japan and Korea that have been developed the field of electronic devices in East Asia. The current research activities are introduced, and the cooperation between JSAP and KPS is deepened in the symposium.

Date and time

September 19 (Wed.) 9:00 -15:00

Venue / Language

Nagoya congress center / English

Invited speakers

From Japan Society of Applied Physics(JSAP) From Korean Physical Society(KPS)

Takuji Hosoi (Osaka Univ.)

"Challenges in SiO₂/SiC interface passivation for SiC power MOSFET"

Kazutoshi Kojima (AIST)

"Challenges in 4H-SiC crystal growth and epitaxy for ultra-high voltage device applications"

Masamichi Akazawa (Hokkaido Univ.)

"Investigation of lightly Mg-ion-implanted GaN using MOS structure"

Manato Deki (Nagoya Univ.)

"Crystal plane dependence of interface states density in c-and m-plane GaN MOS capacitors"

Jae Su Yu (Kyunghee Univ.)

"Wide band gap metal oxide materials for sensing and renewable energy applications"

Jong-Won Lim (ETRI)

"Status of GaN power transistor and MMICs in ETRI"

Jong Kyu Kim (POSTECH)

"Enhanced light extraction from AIGaN deep ultraviolet LEDs"

Yong-Hoon Cho (KAIST)

"Classical and quantum light generation from GaN-based semiconductor nanostructures"

Committees

JSAP

Let's join the symposium!

13.7 Compound and power electron devices and process technology: Masashi Kato, Taketomo Sato, Kozo Makiyama, Kenji Shiojima

Solid state physics and applications subcommittee:

Toshiharu Kubo, Hideto Miyake, Naoki Shigekawa, Sejji Nakamura

Dankook University: Yongmin Kim **KPS**